

**NATIONAL UNIVERSITY OF SINGAPORE**

**EXAMINATION FOR**  
(Semester I: 2014/2015)

**EE2021/EE2021E –DEVICES AND CIRCUITS**

November/December 2014 - Time Allowed: 2.5 Hours

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**MATRIC. NO**

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SECTION A	Marks
Q.1	
Q.2	
Q.3	
Q.4	
Q.5	
Q.6	
SECTION A TOTAL	

SECTION B	Marks
Q.7	
Q.8	
Q.9	
SECTION B TOTAL	

<b>TOTAL MARKS</b>	
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**INSTRUCTIONS TO CANDIDATES:**

1. This paper contains **SECTIONS A and B** and comprises **TWENTY SIX (26)** printed pages.
2. Section A contains **SIX (6)** questions (Total marks of 60) and Section B contains **THREE (3)** questions (Total marks of 40).
3. Answer all questions. **Write your answers on this examination paper.**
4. The questions **DO NOT** carry equal marks.
5. This is a **CLOSED BOOK** examination.
6. Programmable calculators are allowed in this examination.
7. The following information can be used where applicable:

Electronic charge	$q$	=	$1.602 \times 10^{-19} \text{ C}$
Boltzmann constant	$k$	=	$1.381 \times 10^{-23} \text{ J K}^{-1}$
		=	$8.618 \times 10^{-5} \text{ eV K}^{-1}$
Thermal energy ( $T = 300 \text{ K}$ )	$kT$	=	$0.025 \text{ eV}$
Thermal voltage ( $T = 300 \text{ K}$ )	$V_T$	=	$0.025 \text{ V}$
Permittivity of free space	$\epsilon_0$	=	$8.854 \times 10^{-14} \text{ F cm}^{-1}$

**For silicon at 300 K:**

Intrinsic carrier concentration	$n_i$	=	$1.5 \times 10^{10} \text{ cm}^{-3}$
Relative permittivity of silicon	$\epsilon_r (\text{Si})$	=	11.7
Relative permittivity of silicon dioxide	$\epsilon_r (\text{SiO}_2)$	=	3.9

8. A set of formulas and tables is given in a **SEPARATE APPENDIX** for your reference.

## **Section A**

- Q.1** There are two samples of silicon, A and B. Each of them is uniformly doped with both donor and acceptor impurities. Assume that the silicon samples are at thermal equilibrium at 300 K, that all the dopants are ionized, and that the intrinsic carrier concentration,  $n_i = 1.5 \times 10^{10} \text{ cm}^{-3}$ . Complete the table below by filling in the missing values of  $N_D$ ,  $N_A$  and  $n_0$ .

Silicon Sample	Donor conc. $N_D (\text{cm}^{-3})$	Acceptor conc. $N_A (\text{cm}^{-3})$	Equilibrium electron conc. $n_0 (\text{cm}^{-3})$	Equilibrium hole conc. $p_0 (\text{cm}^{-3})$
Sample A	$1 \times 10^{17}$	$9.5 \times 10^{16}$	$5 \times 10^{15}$	$4.5 \times 10^4$
Sample B	$8 \times 10^{15}$	$8 \times 10^{15}$	$1.5 \times 10^{10}$	$1.5 \times 10^{10}$

Is Sample A n-type or p-type? Ans: n - type

Is Sample B n-type or p-type? Ans: Neither. It is intrinsic

Q.2

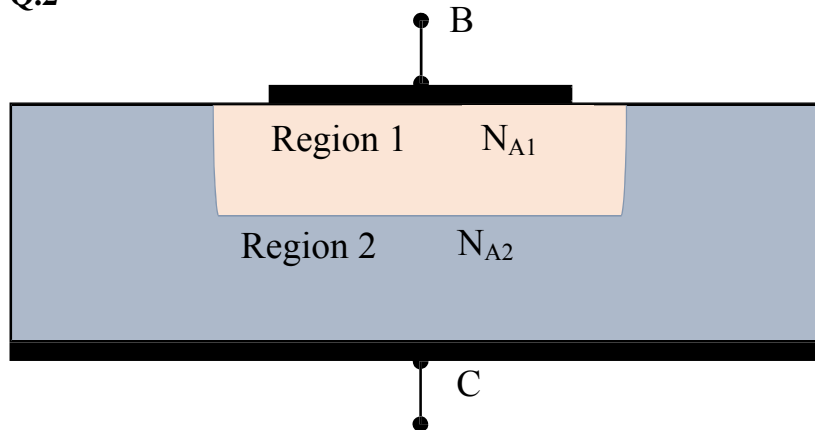


Fig. Q2

A semiconductor wafer has two regions as shown in Fig. Q2. Region 1 is uniformly doped with acceptors with a concentration of  $N_{A1}$  and Region 2 is uniformly doped with acceptors with an acceptor concentration of  $N_{A2}$ . It is given that  $N_{A1} \gg N_{A2}$ . The wafer is at thermal equilibrium at room temperature and with all the dopants ionised. There is no external connection between B and C.

For each of the following statements which refer to the wafer above, circle TRUE if the statement is correct, and FALSE if the statement is wrong.

(Marks will be deducted for each wrong answer you give. No mark will be deducted if you do not answer.)

**[8 marks]**

- i. There is a continuous net motion of holes from Region 2 to Region 1 because of the difference between the doping concentrations in the two regions.  
TRUE/FALSE
- ii. The hole concentrations of Region 1 and Region 2 are equal and have a value somewhere between  $N_{A2}$  and  $N_{A1}$ .  
TRUE/FALSE
- iii. Holes move by diffusion from Region 1 to Region 2 and holes also move by drift from Region 2 to Region 1 but there is no net motion of holes.  
TRUE/FALSE
- iv. A potential barrier exists across the junction between Region 1 and Region 2.  
TRUE/FALSE

**Q.3** Fig. Q3 below shows a single stage amplifier with current mirror biasing.

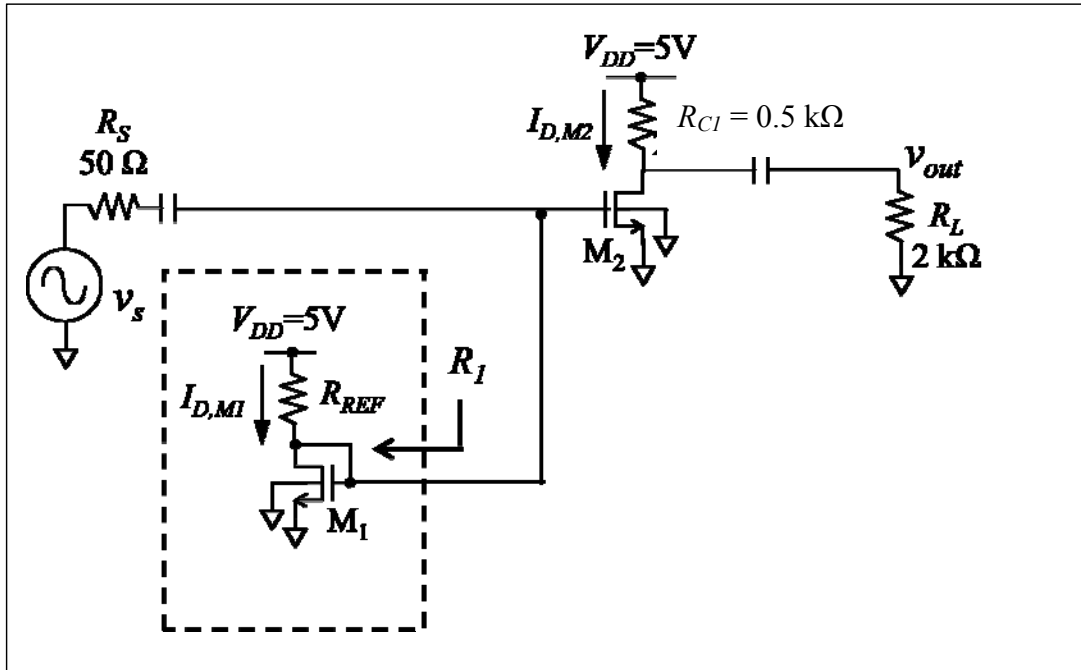


Fig. Q3

For the two n-channel MOSFETs,  $V_{THN1} = V_{THN2} = 1 \text{ V}$ ,  $\lambda_{M1} = \lambda_{M2} = 0$ ,  $K_{n,M1} = \frac{1}{2} \mu_n C_{ox} \left( \frac{W}{L} \right)_{M1} = 2 \text{ mA V}^{-2}$ ,  $K_{n,M2} = \frac{1}{2} \mu_n C_{ox} \left( \frac{W}{L} \right)_{M2} = 4 \text{ mA V}^{-2}$ , where  $\left( \frac{W}{L} \right)_{M2} = 2 \left( \frac{W}{L} \right)_{M1}$ .

(a) Design  $R_{REF}$  such that  $I_{D,M1} = 2 \text{ mA}$ .

[4 marks]

(b) What is the value of  $I_{D,M2}$ ?

[2 mark]

(c) Calculate the small signal parameters of the two MOSFETs, i.e.,  $g_{m,M1}$ ,  $r_{o,M1}$ ,  $g_{m,M2}$ ,  $r_{o,M2}$ .

[4 marks]

(d) Calculate the value of the a.c. equivalent resistance,  $R_I$ , of the circuit enclosed in the dashed box in Fig. Q4.

[3 marks]

(e) Identify the configuration of the single stage amplifier.

[1 mark]

(f) Determine the parameters,  $G_m$ ,  $R_{in}$  and  $R_{out}$  of the two-port network of the amplifier.

[3 marks]

- (a) Design  $R_{REF}$  such that  $I_{D,M1} = 2 \text{ mA}$ .

$$R_{REF} = 1.5 \text{ k}\Omega .$$

- (b) What is the value of  $I_{D,M2}$ ?

$$I_{D,M2} = 4 \text{ mA}.$$

- (c) Calculate the small signal parameters of the two MOSFETs, i.e.,  $g_{m,M1}$ ,  $r_{o,M1}$ ,  $g_{m,M2}$ ,  $r_{o,M2}$ .

$$g_{m,M1} = 4 \text{ mA V}^{-1}.$$

$$r_{o,M1} = \infty$$

$$g_{m,M2} = 8 \text{ mA V}^{-1}.$$

$$r_{o,M2} = \infty$$

- (d) Calculate the value of the a.c. equivalent resistance,  $R_I$ , of the circuit enclosed in the dashed box in Fig. Q.3.

$$R_I = 214.3 \text{ }\Omega.$$

- (e) Identify the configuration of the single stage amplifier.

Common source amplifier.

- (f) Determine the parameters,  $G_m$ ,  $R_{in}$  and  $R_{out}$  of the two-port network of the amplifier.

$$G_m = g_{m,M2} = 8 \text{ mA V}^{-1}.$$

$$R_{in} = R_I // \infty = 214.3 \text{ }\Omega.$$

$$R_{out} = R_C // \infty = 0.5 \text{ k }\Omega.$$

**Q.4** (a) Design the pull down network of the following logic function :

$$Y = \overline{(A + B) \cdot C \cdot (D + E)}.$$

**[4 marks]**

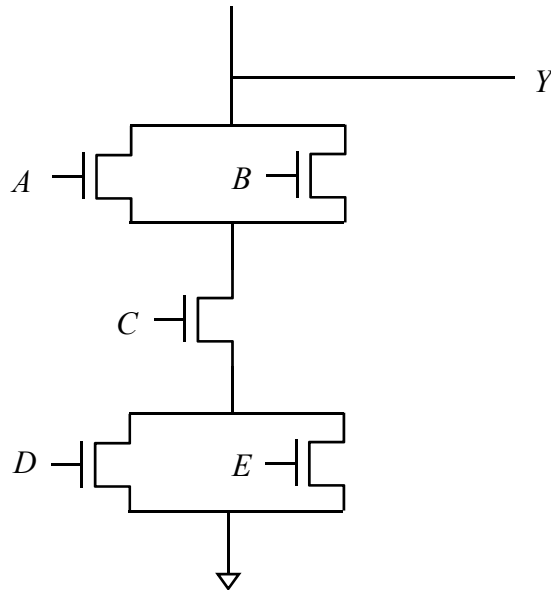
(b) Assume that all the transistors have a sizing of  $(W/L)_{min}$ . Compare the worst case  $t_{pHL}$  of the logic circuit with the  $t_{pHL}$  of an inverter with the same transistor sizing.

**[4 marks]**

(c) Suggest possible sizing of transistors of logic circuit such that its  $t_{pHL}$  equals to an  $t_{pHL}$  of an inverter with sizing of  $(W/L)_{min}$ .

**[2 marks]**

(a)



(b)

$$\frac{t_{pHL,logic}}{t_{pHL,inverter}} = \frac{\left(\frac{W}{L}\right)_{min}}{\frac{1}{3}\left(\frac{W}{L}\right)_{min}} = 3$$

(c) Make the sizing of each of the transistors in the logic circuit equal to  $3(W/L)_{min}$ .



- Q.5** Assume that the AC small signal parameters of the BJT are  $g_{m,Q1}$ ,  $r_{\pi,Q1}$  and  $r_{o,Q1}$ ; and the AC small signal parameters of the MOSFET are  $g_{m,Mj}$ ,  $g_{mb,Mj}$  and  $r_{o,Mj}$ . Write down the expression for the small signal AC equivalent resistances ( $R_{x1}$ ,  $R_{x2}$ ,  $R_{x3}$ ) in the circuit in Fig. Q5.

[9 marks]

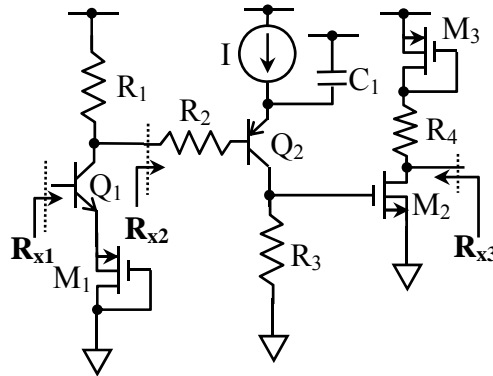


Fig. Q5

$$R_{x1} = r_{\pi,Q1} \left( 1 + g_{m,Q1} \frac{1}{g_{m,M1}} \right)$$

$$R_{x2} = R_2 + r_{\pi,Q2}$$

$$R_{x3} = r_{o,M2} // \left( R_4 + \frac{1}{g_{m,M3}} \right)$$

**Q.6** Show an opamp circuit that can generate the following transfer characteristic in Fig. Q6:

**[8 marks]**

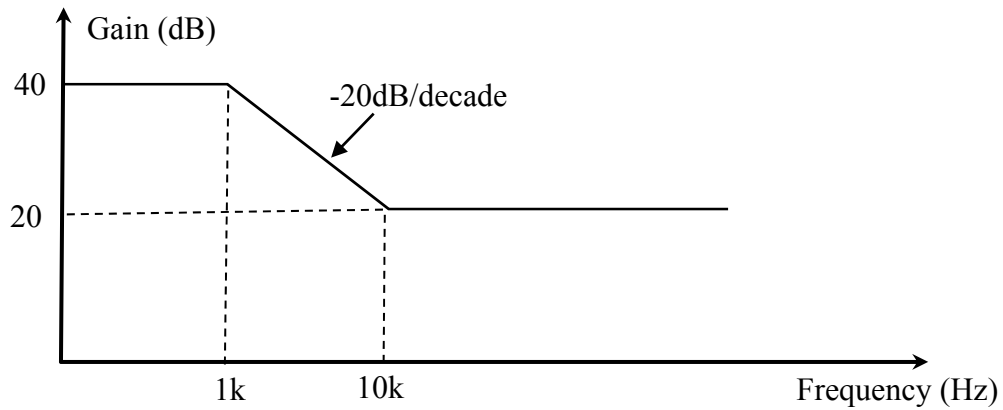
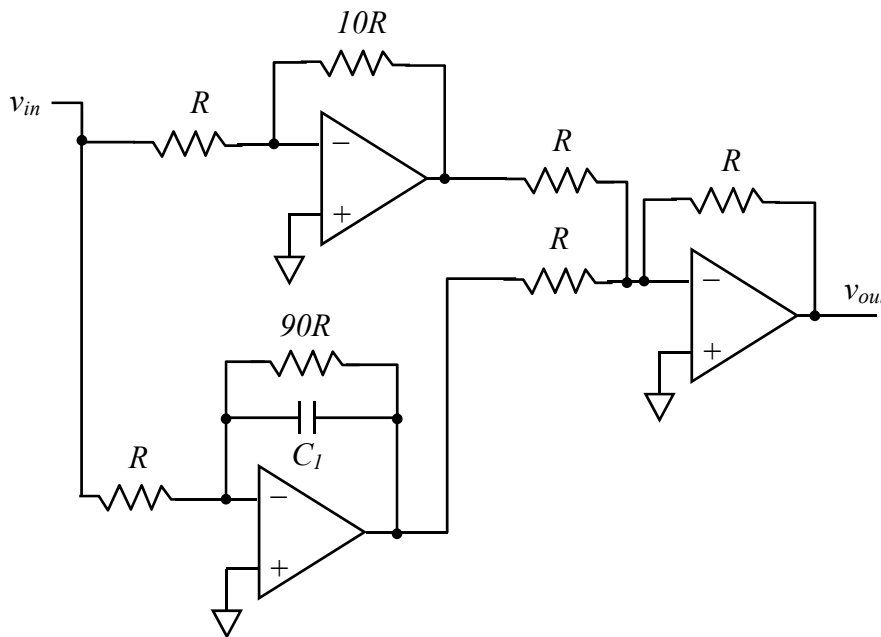


Fig. Q6

[Note :  $\text{Gain(dB)} = 20 \times \log_{10}(V_{\text{out}}/V_{\text{in}})$ . Hence, 40dB is equivalent to  $V_{\text{out}}/V_{\text{in}}=100$ , 20dB is equivalent to  $V_{\text{out}}/V_{\text{in}}=10$ ]



$$C_1 = \frac{2\pi 1k}{90R}$$

## **Section B**

**Q.7** The minority carrier concentration distributions in the neutral region of the emitter, base and collector of a bipolar junction transistor (BJT) are shown in Fig. Q7. The emitter, base and collector are each uniformly doped. The thermal equilibrium electron concentration in the emitter and collector are  $n_{E0} = 11.25 \text{ cm}^{-3}$  and  $n_{C0} = 2.25 \times 10^5 \text{ cm}^{-3}$ , respectively. The neutral base width,  $w_B = 1 \text{ }\mu\text{m}$ , and the thermal equilibrium hole concentration in the base,  $p_{B0}$ , has a magnitude between  $n_{E0}$  and  $n_{C0}$ . In Fig. Q7,

- $p_B(x=0)$  is the hole concentration in the neutral base region, at the edge of the emitter-base space charge region (SCR).
- $n_E(x'=0)$  is the electron concentration in the neutral emitter region, at the edge of the emitter-base SCR.
- $p_B(x=w_B) \approx 0$  is the hole concentration in the neutral base region, at the edge of the base-collector SCR.
- $n_C(x''=0) \approx 0$  is the electron concentration in the neutral collector region, at the edge of the base-collector SCR.

It is known that one of the junctions of the BJT is forward biased with a voltage of magnitude 0.7 V across it, while the other junction is reverse biased with a voltage of magnitude 2 V across it. You are also given that the base-collector junction capacitance,  $C_j$ , under the above given biased condition is 0.5 times that at zero bias.

(a) Is the BJT operating in the forward active mode? Explain your answer.

[2 marks]

(b) What are the doping type and doping concentration of the collector?

[3 marks]

(c) Determine the built-in voltage,  $V_o$ , of the base-collector junction?

[3 marks]

(d) What is the value of  $p_B(x=0)$ ?

[3 marks]

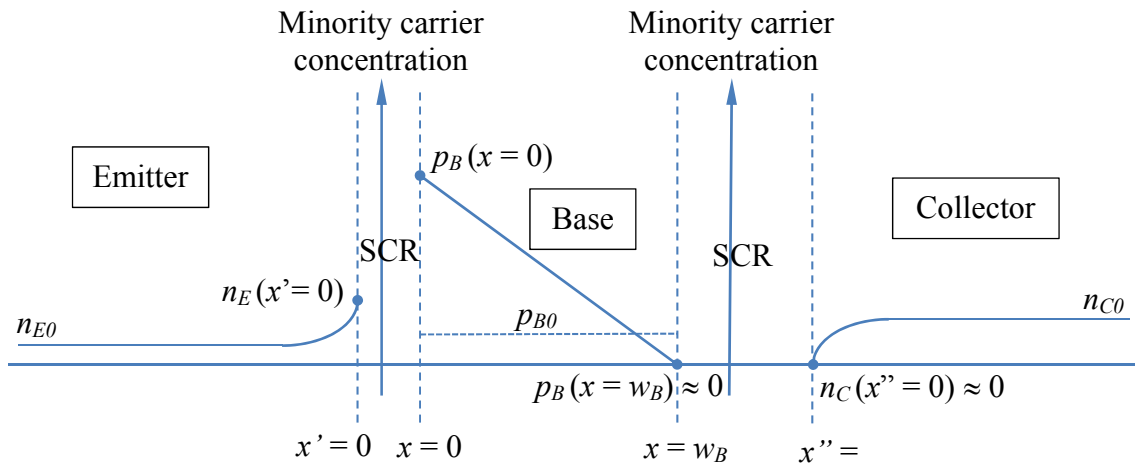


Fig. Q7

- (a) Yes.
- (b) p-type  $N_{AC} = 10^{15} \text{ cm}^{-3}$
- (c)  $V_o = 0.67 \text{ V}$
- (d)  $p_B(x=0) = 3.33 \times 10^{15} \text{ cm}^{-3}$

**Q.8** The Zener diode circuit within the dashed box shown in Fig. Q8 is used to provide the DC biasing to the transistor circuit. The breakdown voltage of the Zener diode,  $D_I$ , is 5 V. The transistor,  $Q_I$ , has  $\beta = 100$  and  $V_A = 100$  V. You may assume  $I_{R1} \approx I_{R2} \gg I_B$ .

(a) Determine the current supplied by the Zener diode circuit  $I_L$ .

[4 marks]

(b) What is the maximum allowable  $R_S$  such that the Zener diode will function properly?

[3 marks]

(c) What is the impact of choosing  $R_S$  much smaller than the value in part (b).

[2 marks]

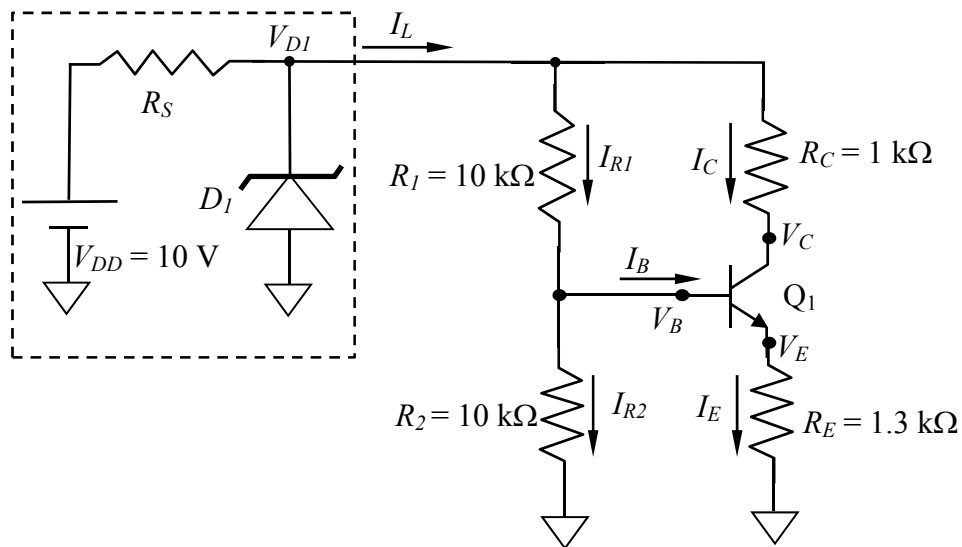


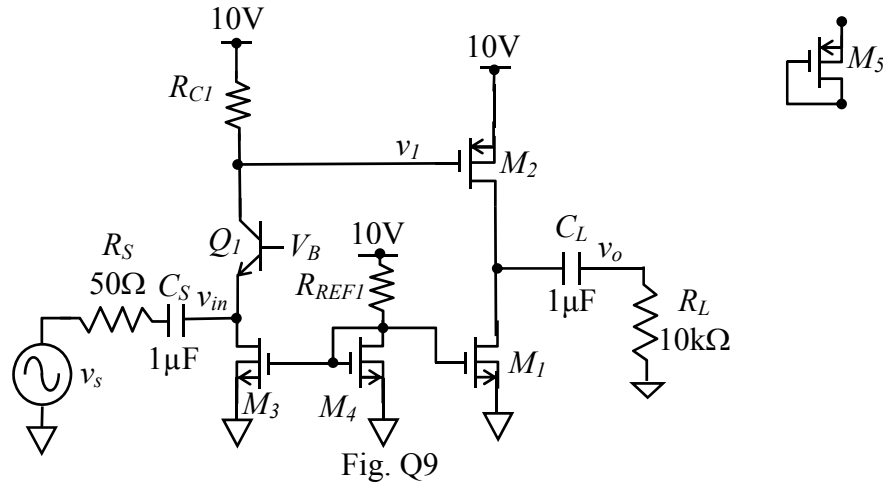
Fig. Q8

(a)  $I_L = 1.63$  mA.

(b) Maximum  $R_S$  allowable = 3.07 kΩ.

(c) The current through the Zener diode will be much large than the value corresponding to  $R_S = 3.07$  kΩ.

## Q.9



In the two-stage amplifier circuit shown in Fig. Q9, assume that the pnp BJT, the NMOS transistors and the PMOS transistors have the following device parameters:

- $V_A = 100$  V and  $\beta = 100$  for the BJT,  $Q_1$ ;
- $K_n = 2\text{m A/V}^2$ ,  $V_{THN} = 1$  V,  $\lambda_n = 0.001\text{V}^{-1}$  and no body effect for the NMOS transistors,  $M_3$  and  $M_4$ .
- $K_p = 2\text{m A/V}^2$ ,  $V_{THP} = -1$  V,  $\lambda_p = 0.001\text{V}^{-1}$  and no body effect for the PMOS transistors,  $M_1$  and  $M_2$ .

Further assume that  $R_{REF1}$  is chosen such that  $M_1$ ,  $M_3$  and  $M_4$  each has a drain current of 1mA. (You are not required to find  $R_{REF1}$ .)

- (a) Identify the configuration of each stage of the multi-stage amplifier.

**[2 marks]**

- (b) Estimate the small signal parameters of  $M_2$ , i.e.  $g_{m,M2}$ , and  $r_{o,M2}$  and the small signal parameters of  $Q_1$ , i.e.,  $g_{m,Q1}$ ,  $r_{\pi,Q1}$ ,  $r_{o,Q1}$ .

**[3 marks]**

- (c) Design  $R_{C1}$  to ensure that  $M_2$  has the same current as  $M_1$  assuming these transistors are operating in the saturation region.

**[2 marks]**

- (d) Estimate the overall gain, i.e.,  $v_o/v_s$ .

**[6 marks]**

- (e) What is the minimum  $V_B$  value allowed such that  $M_3$  is operating in saturation region?

**[4 marks]**

- (f) If  $R_{C1}$  is replaced with  $M_5$ , would it create any biasing issue? Would the overall gain be larger or smaller?

**[3 marks]**

(a) CB-CS

(b)

$$g_{m,M2} = 2.8\text{mA/V}, r_{o,M1} = 1\text{M}\Omega$$

$$g_{m,Q1} = 40\text{mA/V}, r_{\pi,Q1} = 2.5\text{k}\Omega, r_{o,Q1} = 100\text{k}\Omega$$

(c)  $R_{CI} = 1,71\text{ k}\Omega$

(d)  $v_o / v_s = 638.4$

(e)  $V_{B,min} = 1.407\text{ V}$

(f) Biasing would not be an issue. Overall gain would be smaller.

**END OF PAPER**